אוניברסיטת בן-גוריון בנגב
Ben-Gurion University of the Negev

Nano-Fabrication Center

AJA egun & thermal ATC-2036-E-T

Description

The combination of an electron gun with an integrated thermal deposition system offers a powerful solution for precise thin film deposition. The e-gun generates a high-energy electron beam that can heat and evaporate target materials, enabling controlled vaporization. The system also enhances control over film thickness, composition, and uniformity. This setup is suitable for semiconductor manufacturing, optics, and aerospace applications, where high-quality coatings with specific material properties are required.

Specifications/Capabilities

Wafer size: up to 6” (152.4mm)
Tilted mechanism for angled deposition (-90 to 90 degrees)
Water cooled substrate with rotation feature of up to 20 rpm available
The system can be configured for high rate, low rate, multi-layer, and co-deposition applications.
variety of evaporation sources, such as linear, multi-pocket, UHV e-beam sources, thermal evaporation sources (k-cell, resistive boat, Radak, low-temp organic), and magnetron sputter sources.

Link

https://www.ajaint.com/atc-e-series-e-beam-evaporation-systems.html